

# Status of the Laboratory

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Universität Hamburg  
Institut für Experimentalphysik  
Detektorlabor

D. Eckstein, E. Fretwurst, V. Khomenkov, R. Klanner, G. Lindström, A. Srivastava, G. Steinbrück  
J. Becker, M. Bock, A. Junkes, J. Lange

1<sup>st</sup> Detector Workshop of the Helmholtz Alliance *Physics at the Terascale*  
Karlsruhe, 3<sup>rd</sup> and 4<sup>th</sup> of April 2008

## Outline:

- Projects
- Aims
- Expertise and Infrastructure
- Examples

# Detector R&D Projects

## funding within the Alliance:

### **WP1: The Virtual Laboratory for Detector Technologies**

- **WP1.2: Sensors: Materials, Design and Characterisation**
- **WP1.3: Detector Systems: Development, Infrastructure and Testing**

### **WP2: Detector R&D Projects**

- **WP2.4: Radiation hard silicon sensors for the sLHC**  
time/annealing for different materials

## other:

- **CMS (funded by BMBF)**
- **HPAD-XFEL (with Bonn, PSI, DESY)**
- **Marie Curie International Training Network MC-PAD (with CERN, DESY, ...)**
- **FP7 Proposal**

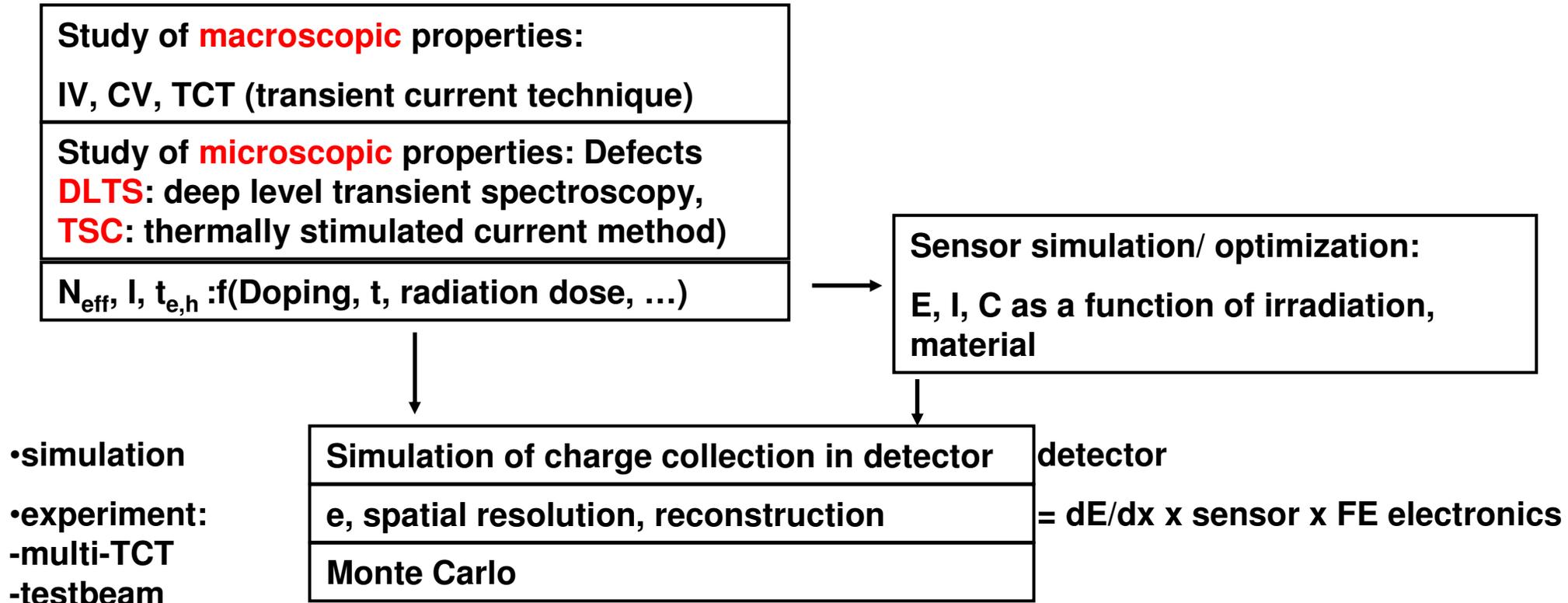
## Aims

- quantitative understanding of Si sensor performance in harsh radiation environment
- improve sensor performance by defect engineering
- optimize sensor design (for given material, dose/fluence)

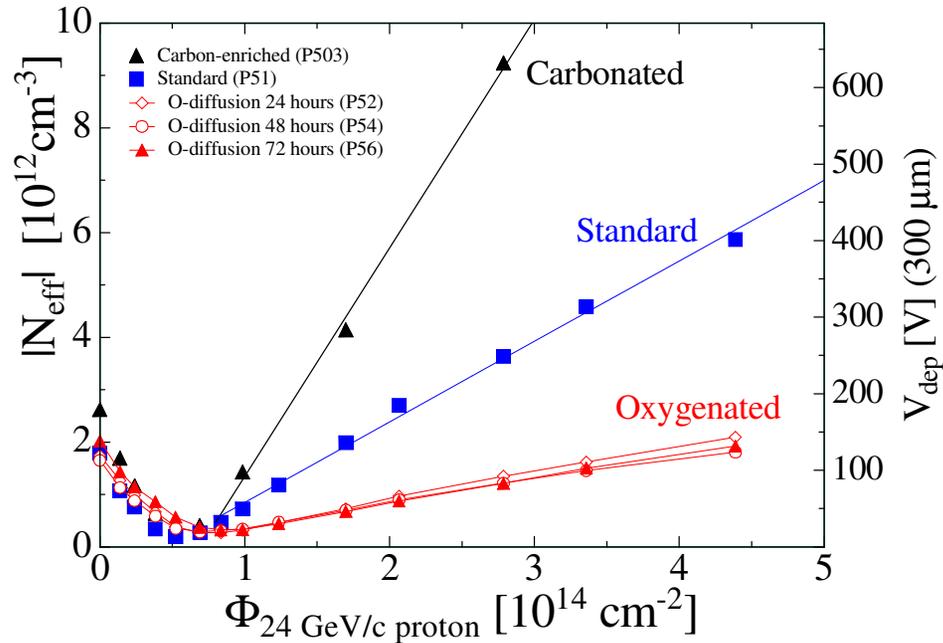
# Expertise and Infrastructure

- I. Irradiation campaigns  
(CERN, Ljubljana, Stockholm, Darmstadt, Karlsruhe, DORIS,...)
- II. Macroscopic damage vs. time/annealing for different materials
  - Dark current → I/V
  - $N_{\text{eff}} \rightarrow V_{\text{dep}} \rightarrow C/V$
  - CCE →  $\tau_{\text{eff}} \rightarrow TCT$
  - $N_{\text{ox}}, N_{\text{eff}} \rightarrow$  sensor stability → C/V
  - evolution with time → annealing
  - overall performance → multi-channel TCT (*new*)  
testbeam
- III. Microscopic damage vs. time/annealing for different materials: TSC, DLTS
  - characterisation of damage levels
  - kinetics vs. time/annealing
  - relate to macroscopic damage
- IV. Incorporate results I. and II. into simulation of
  - sensor “static”
  - charge collection
  - ➔ reliable prediction of long-term performance in the experiments environment

# Strategies



# Example: Epitaxial Silicon Detectors

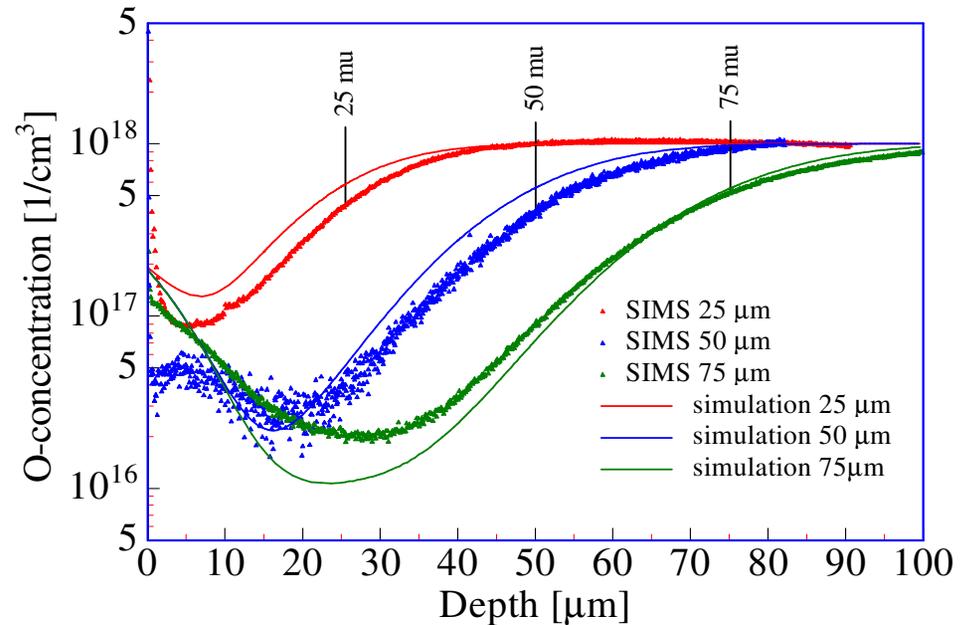


- for LHC oxygenated Si chosen
- based on findings of RD48

Now for SLHC: try naturally oxygen rich material  
 → epitaxial and MCz materials  
 try thin material (trapping!)

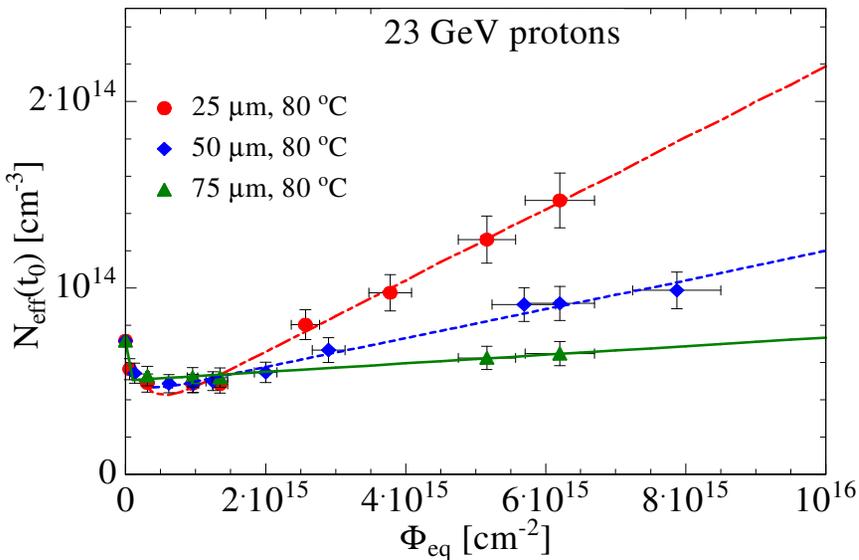
## • Epitaxial silicon

- Chemical-Vapor Deposition (CVD) of Silicon
- CZ silicon substrate used → diffusion of oxygen
- Growth rate about 1 μm/min
- Excellent homogeneity of resistivity



$$[O](25\mu\text{m}) > [O](50\mu\text{m}) > [O](75\mu\text{m})$$

# Epitaxial Silicon contd...



$N_{\text{eff}}(t_0)$ : Value taken at annealing time  $t_0$  at end of short term annealing (10 min @ 80°C)

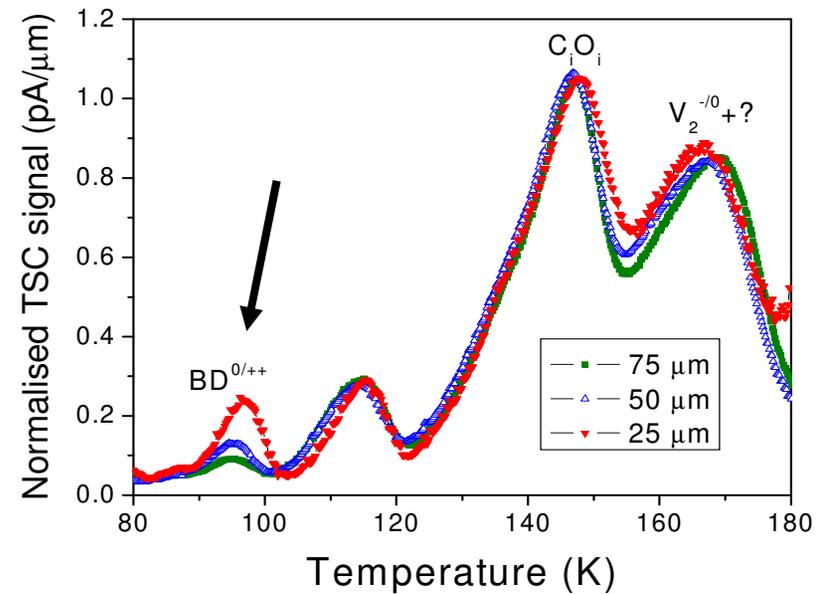
No SCSI after proton (and neutron) irradiation

Introduction of shallow donors overcompensates creation of acceptors

$N_{\text{eff}}(25\mu\text{m}) > N_{\text{eff}}(50\mu\text{m}) > N_{\text{eff}}(75\mu\text{m})$

**Strong correlation between [O]-[BD]- $N_{\text{eff}}$   
generation of O (dimer?)-related BD reason for  
superior radiation tolerance of EPI Si detectors**

## Defect spectroscopy after p-irradiation (TSC)

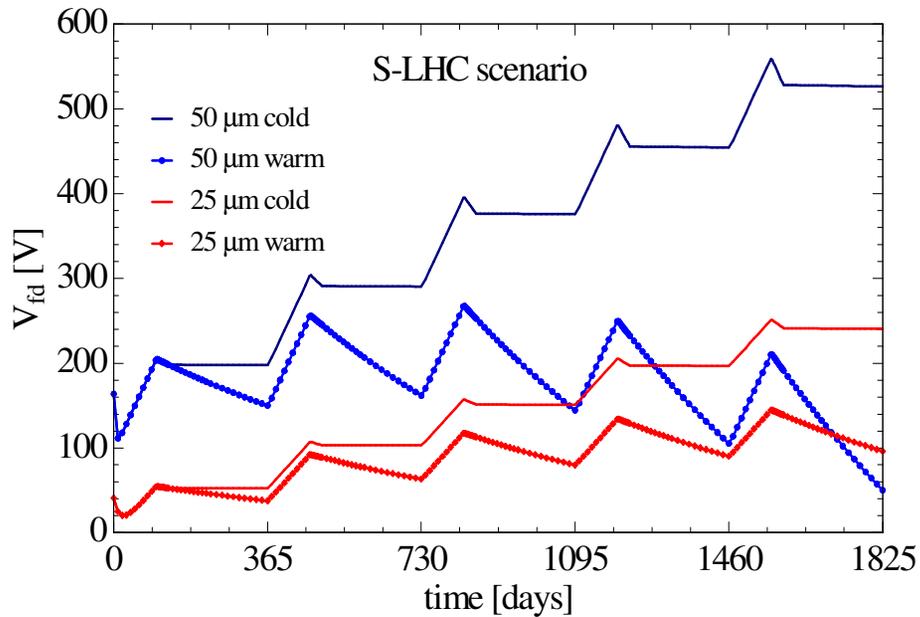


Generation of shallow donors BD (Ec-0.23 eV) strongly related to [O]

$[\text{BD}](25\mu\text{m}) > [\text{BD}](50\mu\text{m}) > [\text{BD}](75\mu\text{m})$

G.Lindstroem et al., NIM A568 (2006) 66-71

# Example: SLHC operating scenario – simulation and experiment

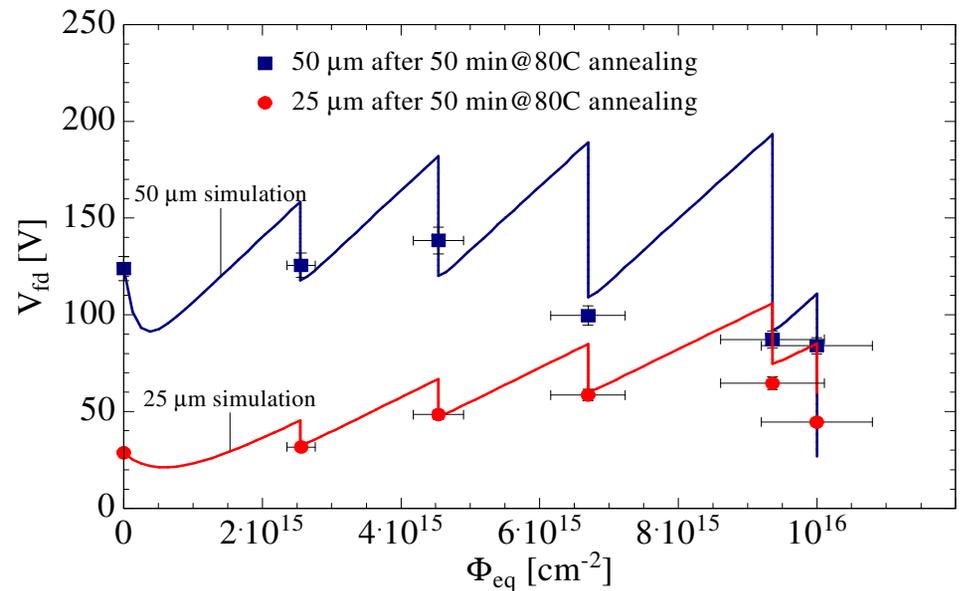


- Experimental parameter:
- Irradiation: fluence steps  $\approx 2.2 \times 10^{15} \text{ cm}^{-2}$   
irradiation temperature  $\approx 25^\circ\text{C}$
- After each irradiation step  
annealing at  $80^\circ\text{C}$  for 50 min,  
corresponding 265 days at  $20^\circ\text{C}$

**Excellent agreement between  
experimental data and simulated results**

- **Simulation + parameters reliable!**

- Radiation @ 4cm:  $\Phi_{eq}(\text{year}) = 3.5 \times 10^{15} \text{ cm}^{-2}$
- SLHC-scenario:
  - 1 year = 100 days beam ( $-7^\circ\text{C}$ )
  - 30 days maintenance ( $20^\circ\text{C}$ )
  - 235 days no beam ( $-7^\circ\text{C}$  or  $20^\circ\text{C}$ )
- **Operation without cooling is beneficial!!!**



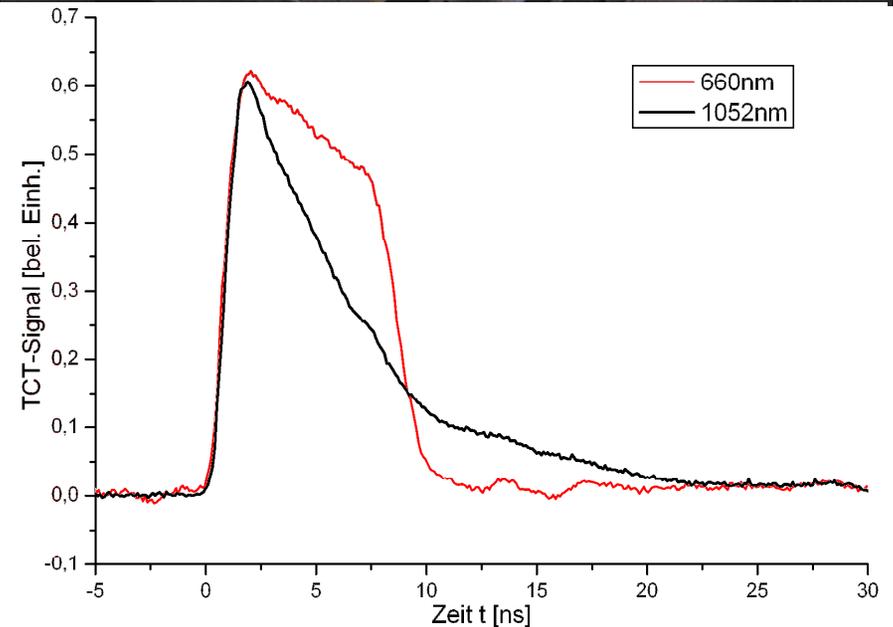
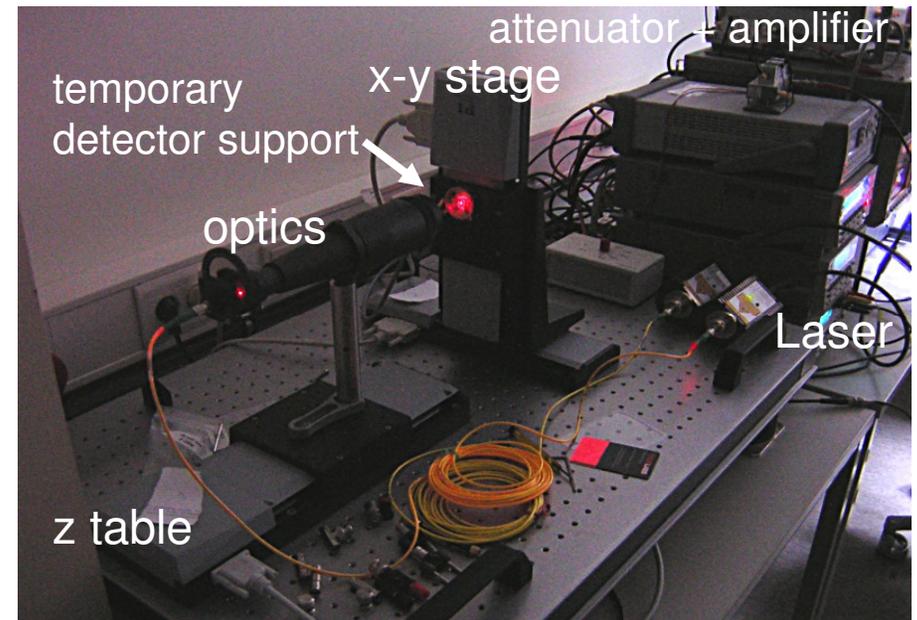
G.Lindstroem et al., NIM A568 (2006) 66-71

# New: multi-channel TCT

**Goal:** Time-resolved measurement of charge collection in Si-pixel and strip detectors in multiple channels up to very high charge densities. fine-grain position and angle scans.

Multi-TCT under construction in Hamburg:

- ps laser (1052 nm and 660 nm), <90ps,  $W_{\max} \sim 200\text{pJ}$ , spot size <10  $\mu\text{m}$  (red)
- penetration depth 3  $\mu\text{m}$  (red), 1000 $\mu\text{m}$  (IR)
- fast amplifiers (miteq)
- data acquisition with fast oscilloscope (500 MHz, 1GS/channel), possible upgrade to digitizer cards with up to 20 ch, synchronized
- cooled detector support (Peltier)



## Aims:

- quantitative understanding of Si sensor performance in harsh radiation environment
- improve sensor performance by defect engineering
- optimize sensor design (for given material, dose/fluence)

## Techniques:

- I/V, C/V, TCT, multi-TCT, DLTS, TSC

**BACKUP**

# Silicon Detectors for Vertexing and Tracking

## Silicon detectors:

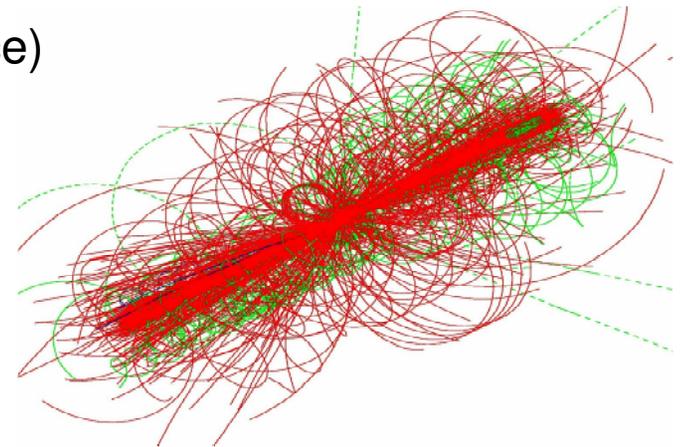
- ✓ are used for vertexing, lifetimes, triggering, tracking, even  $dE/dx$
- ✓ are used in all current HEP experiments
- ✓ detect MIPs
- ✓ are fast ( $\sim 10\text{ns}$ ) and precise ( $\sim 10\mu\text{m}$ )
- ✓ (crazy geometries, run in vacuum, cover large surface)
- ✓ are radiation tolerant

## LHC starting 2008:

- Luminosity  $L = 10^{34} \text{ cm}^{-2}\text{s}^{-1}$
- in 10 years ( $500 \text{ fb}^{-1}$ )  $\Phi (r=4\text{cm}) \sim 3 \cdot 10^{15} \text{ cm}^{-2}$
- Oxygenated Silicon (ROSE-Collaboration RD48)
- replacement might be necessary

## sLHC starting 201x:

- Luminosity  $L = 10^{35} \text{ cm}^{-2}\text{s}^{-1}$
- in 5 years ( $2500 \text{ fb}^{-1}$ )  $\Phi (r=4\text{cm}) \sim 1.6 \cdot 10^{16} \text{ cm}^{-2}$
- new materials/technologies under investigation (RD50 Collaboration)



# Radiation Damage in Silicon Sensors

Two general types of radiation damage:

- Bulk damage due to Non Ionizing Energy Loss

- displacement damage, built up of crystal defects –

- Change of **Effective Doping Concentration**  $N_{eff}$

- type inversion

- higher depletion voltage → possibly under-depletion → loss of signal, increased noise

- junction moves from p+ to n+ side

- ← influenced by impurities in Si (oxygen, carbon,...) ← **defect engineering, material dependence!**

- Increase of **Leakage Current**

- shot noise → thermal runaway, power consumption → hard to bias

- ← temperature dependent ← need cooling

- Increased carrier **Trapping**

- Charge loss → at  $10^{16}\text{cm}^{-2}$   $\lambda \leq 20\mu\text{m}$  charge collection distance!

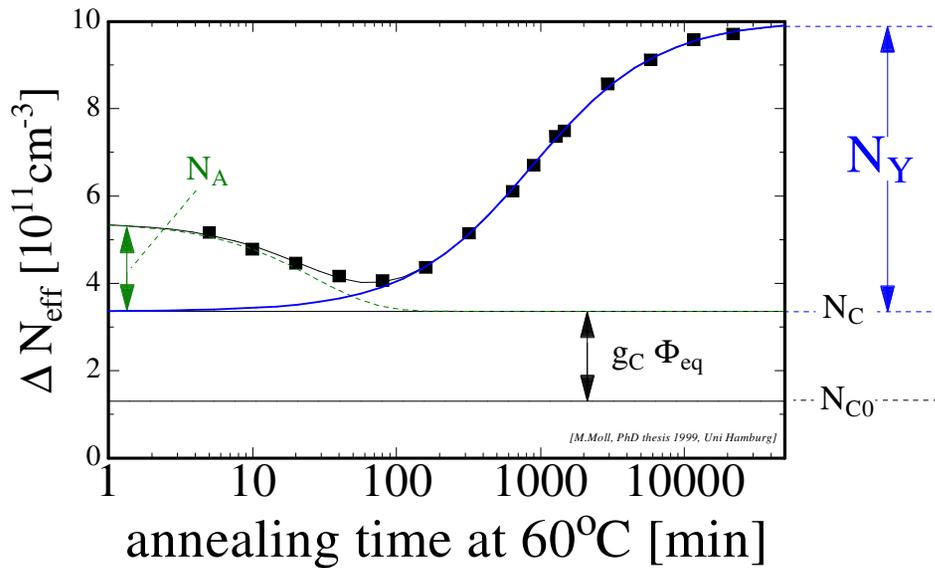
- Surface damage due to Ionizing Energy Loss

- accumulation of charge in the oxide ( $\text{SiO}_2$ ) and Si/ $\text{SiO}_2$  interface

- interstrip capacitance (noise factor), breakdown behavior, ...

# Radiation Damage - Annealing

## Change of $N_{\text{eff}}$ with time

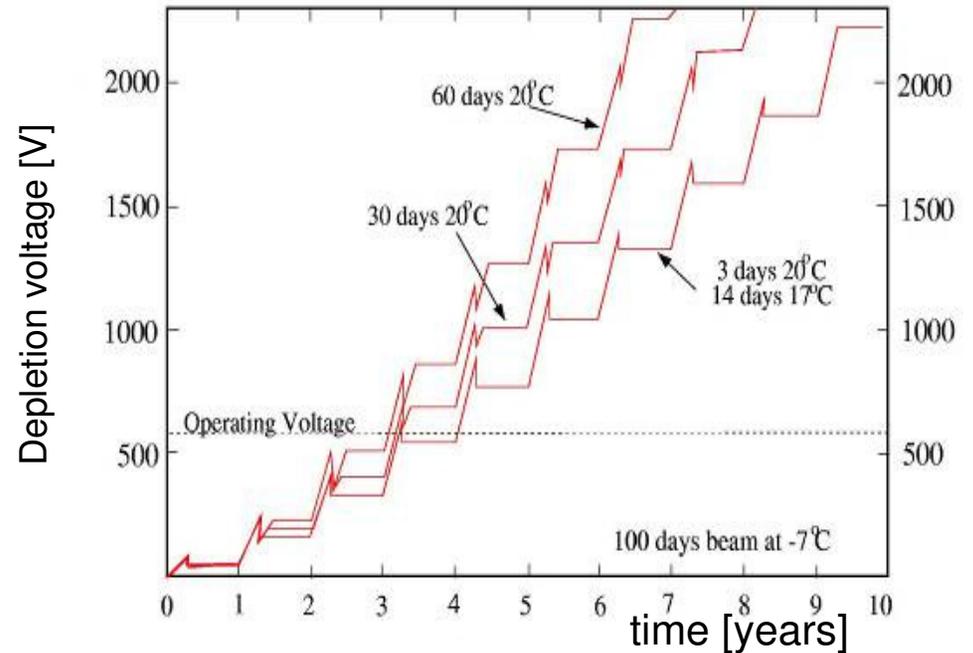


Short term: “Beneficial annealing”

Long term: “Reverse annealing”

- time constant depends on temperature:

- ~ 500 years      (-10°C)
- ~ 500 days     ( 20°C)
- ~ 21 hours      ( 60°C)



## Consequence:

**Cool Detectors even during beam off  
alternative: acceptor/donor compensation by  
defect engineering**

